



[2345/108]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Hans Wilfried Peter KOOPS
Serial No. : 09/462,283
Filed : March 29, 2000
For : METHOD FOR PRODUCING ACTIVE OR PASSIVE
COMPONENTS ON A POLYMER BASIS FOR
INTEGRATED OPTICAL DEVICES
Art Unit : 1746
Examiner : S. Ahmed

Commissioner of Patents
Washington, D.C. 20231

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Signature:

Linda M. Shudy

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AMENDMENT

SIR:

In response to the Office Action having mailing date April 24, 2002, please reconsider
the above-identified application based on the following.

IN THE CLAIMS:

Please amend claim 7 without prejudice as follows:

7. (Amended) A process for fabricating active and passive polymer-based components for use
in integrated optics according to a principle based on one of a gas-phase diffusion and a
liquid-phase diffusion, comprising the steps of:

depositing onto an optoelectronic component at least one patternable polymer resist
layer that is highly sensitive and that effects an intense polymerization when exposed;
producing an etching mask by exposing defined regions of the at least one patternable
polymer resist layer corresponding to a later component;
transferring a geometry of the etching mask through a high-grade anisotropic deep
etching into unprotected regions of the at least one patternable polymer resist layer located
underneath the etching mask, wherein an etching agent is used that avoids attacking a silicon